INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01150103	Serial No.: 10/771,043
	Applicant(s): Gurtej S. Sandhu	Confirmation No.: 1538
	Application Filing Date: February 3, 2004	Group: 1743
	Information Disclosure Statement mailed: June 16, 2004	

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
		5,653,807	08/05/97	Crumbaker			

FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
YG	X	1,576,658	08/01/69	France (w/abstract)			X	
YG	X	2-293644	12/04/90	Japan (w/abstract)			X	
↓	X	3-48748	03/01/91	Japan (w/abstract)			X	
considered YG	~~X~~	~~2-69658~~	~~03/08/90~~	~~Japan (w/abstract)~~				X

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
YG	X	Akinfieva, T.A., "Basis for the maximum allowable concentration of ruthenium dioxide in the air of work areas," *Gigiena Truda i Professional'nye Zabolevaniya*, 1981:46-47 (English Abstract Included)
|	X	Crawford et al., "Use of the Hazop Analysis for Evaluation of CVD reactors," *Journal de Physique IV*, September 1991: C2-459- C2-466.
|	X	Gale et al., "Interaction of Safety and the facility for Photovoltaic R & D," *American Institute of Physics Conference Proceedings*," 1988;66:145-151
|	X	Koda et al., "Radioactivation determination of ruthenium," *Kyoto Daigaku Genshiro Jikkensho Gakujutsu Koenkai Koen Yoshishyu*, 1976;10:25-27. (English Translation)
|	X	Lu et al., "Epitaxial growth of RuO_2 thin films by metal-organic chemical vapor deposition," *Thin Solid Films*, 1999;340:140-144.
↓	X	Orlow et al., "Detection of Ruthenium in Platinum Alloys," *Chemiker-Zeitung*, 1908;32:77. (English Translation)

EXAMINER	Date Considered
Yelena Gak	08/06/04

*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

OMB No. 0651-0011

INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01150103	Serial No.: 10/771,043
	Applicant(s): Gurtej S. Sandhu	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed:	April 29, 2004

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
YG		3,585,073	06/15/71	Veenstra et al.			
		3,890,703	06/75	Frazee et al.			
		4,433,320	02/21/84	Murata et al.			
		4,442,422	04/10/84	Murata et al.			
		4,677,416	06/30/87	Nishimoto et al.			
		4,911,892	03/27/90	Grace et al.			
		5,147,737	09/15/92	Post et al.			
		5,331,287	07/19/94	Yamagishi et al.			
		5,337,018	08/09/94	Yamagishi			
		5,756,879	05/26/98	Yamagishi et al.			
		5,857,250	01/12/99	Riley et al.			
		5,906,726	05/25/99	Schneider et al.			
		6,280,604	08/28/01	Allen et al.			
		6,436,246	08/20/02	Sandhu			
		6,479,297	11/12/02	Sandhu			
V		6,689,321	02/10/04	Sandhu			
		US 2003/0138958	07/24/03	Blalock			

FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
		1,151,482	05/07/69	Great Britain				
		1,576,658	08/01/69	France (w/abstract)				X

EXAMINER	Date Considered
Yelena Gak	Parent case 05/26/03

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OMB No. 0651-0011

INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01150103	Serial No.: 10/771,043
	Applicant(s): Gurtej S. Sandhu	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed:	April 29, 2004

		2-293644	12/04/90	Japan (w/abstract)				X
		386,660	09/12/90	EP (w/abstract)				X
		3-48748	03/01/91	Japan (w/abstract)				X
		60-210752	10/85	Japan (w/abstract)				X
		2-69658	03/90	Japan				X

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
YG		Aizenshtein et al., "Method of measurement of the rate of deposition of pure metals from the gas phase," *Chem. Abstr.*, 1966; *64*: abstract 1747e.
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		Kawahara et al., "(Ba,Sr)TiO_3 Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," *Jpn Journ Appl Phys*, 1996;*35* (Part 1, No. 9B): 4880-4885.
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		Koda et al., "Radioactivation determination of ruthenium," *Chem Abstr*, 1979;*90*: abstract 114382q.

EXAMINER	Date Considered
Yelena Gakh	12/15/03 05/26/03 11/17/03

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OMB No. 0651-0011

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	Applicant(s): Gurtej S. Sandhu	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed:	April 29, 2004

Examiner Initial	Copy Enclosed	Document Description
YG		Koda et al., "Radioactivation determination of ruthenium," *Kyoto Daigaku Genshiro Jikkensho Gakujutsu Koenkai Koen Yoshishu*, 1976;*10*: 25-27.
		Kolesov et al., "Role of surface moisture of samples in the determination of volume resistivity of polymers," *Chem Abstr*, 1989; *110*: abstract 213848j.
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N		Schepis et al., "Influence of deposition rates and thickness on the electrical resistivity and thermoelectric power of thin iron films," *Thin Solid Films*, 1994;251: 99-102.

EXAMINER	Date Considered
Yelle Yale	the parent case

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OMB No. 0651-0011

INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.01150103	Serial No.: 10/771,043
	Applicant(s): Gurtej S. Sandhu	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
	Information Disclosure Statement mailed:	April 29, 2004

Examiner Initial	Copy Enclosed	Document Description
YG		Takayama et al., "Gas-Sensitive Ag Ion Conduction in Semiconducting ZnO Thin Films," *Solid State Ionics*, 1989; *35*: 411-415.
YG		Tardif et al., "Monitoring of metallic contamination by direct and indirect analytical methods application to cleaning processes in IC manufacturing," *Chem Abstr.*, 1995;123: abstract 328642y.
		Trent et al., "Ruthenium Tetraoxide Staining of Polymers for Electron Microscopy, " *Macromolecules*, 1983; *16*: 589-598.
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✓		Yuan et al., "Low-Temperature Chemical Vapor Deposition of Ruthenium Dioxide from Ruthenium Tetroxide: A Simple Approach to High Purity RuO_2 Films," *Chem Mater*, 1993; *5*: 908-910.

EXAMINER	Yelw Gak	Date Considered	the parent case

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